REMARKS

This application has been reviewed in light of the Office Action dated June 5, 2007. Claims 1, 3, and 8 are presented for examination. Claims 1 and 3 have been amended to define more clearly what Applicants regard as their invention. Claims 5, 6, and 7 have been cancelled without prejudice and disclaimer of subject matter, and will not be addressed further herein.

New Claim 8 has been added to provide Applicants with a more complete scope of protection. Claims 1, 3, and 8 are in independent form. Favorable reconsideration is requested.

Claims 1, 3, 5, and 6 were rejected under 35 U.S.C. 103(a) as being obvious over U.S. Patent Application Publication No. 2001/0039161 (*Sato*) in view of U.S. Patent No. 6,638,128 (*Suzukt*).

According to an aspect of the invention recited in Claim 1, a second temperature adjusting mechanism is for adjusting temperature of an area of the substrate outside the vessel, and a temperature of the second temperature adjusting mechanism is higher than that of the first temperature adjusting mechanism. See, e.g., the attached sketch which is submitted for illustrative purposes only, and which is not intended to limit the scope of the claimed invention.

The Office Action concedes that Sato does not disclose or suggest "the second temperature adjusting mechanism for adjusting the temperature of the further region."

The Office Action cites col. 25, line 50 to col. 26, line 10 of Suzuki, as

teaching "a second temperature adjusting mechanism". However, this assertion is incorrect.

Col. 25, lines 43-48 states the following:

"The atmosphere for performing the activation can be realized by <u>disposing</u> the <u>multi-electron source substrate 102</u> in the vacuum chamber 101 as similar to FIG. 1. A difference of this embodiment from the foregoing embodiment is the substrate supporting base 103, and FIG. 28 shows the substrate supporting base in this embodiment."

(Emphasis added).

That is, as taught therein, a substrate supporting base 103 in Fig. 28 is wholly and completely included and contained within a vacuum chamber 101, in the same manner as the substrate supporting base 103 in Fig.1. Nothing has been found, or pointed out, in either Sato or Suzuki that would teach or suggest a second temperature adjusting mechanism for adjusting temperature of an area of the substrate <u>outside the vessel</u>, as set forth in Claim 1. Accordingly, Claim 1 is believed to be clearly patentable over those references, whether considered separately or in combination.

According to an aspect of the invention recited in Claim 3, heating is provided to an area of the part of the substrate inside the vessel by a first temperature adjusting mechanism, and an area of the substrate outside the vessel by a second temperature adjusting mechanism, wherein a temperature of the second temperature adjusting mechanism is higher than that of the first temperature adjusting mechanism.

Added Claim 8 is directed to a method reciting, in part, "heating an area of the part of the substrate inside the vessel by a first temperature adjusting mechanism, and an area of the substrate outside the vessel by a second temperature adjusting mechanism" (emphasis added). For similar reasons as those argued above with respect to Claim 1, Claims 3 and 8

also are believed to be clearly patentable over Sato or Suzuki, whether considered

separately or in combination, because those references do not teach or suggest the

foregoing respective recitations of those claims.

The other, dependent claims in this application each depend from Claim 1,

and therefore partake in its patentability. Nonetheless, given that each dependent claim

recites an additional aspect of the invention, the individual reconsideration of each on its is

respectfully requested.

In view of the foregoing remarks, Applicants respectfully request favorable

reconsideration and allowance of the present application.

Applicants' undersigned attorney may be reached in our New York Office

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Respectfully submitted,

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-7-

